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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Hiroshi MASHIMA, et al.

SERIAL NUMBER: 10/518,371 GROUP: 1715

FILED: December 28, 2004 EXAMINER: Kelly M. Gambetta

FOR: METHOD FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION AND APPARATUS FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION

**REQUEST TO CORRECT TITLE OF INVENTION**

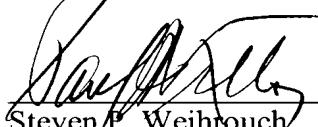
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SIR:

In the matter of the above-identified application for patent, we hereby request correction of your records to reflect the correct title of the invention. The title of the invention should read as follows: **METHOD FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION AND APPARATUS FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION.**

Respectfully Submitted,

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